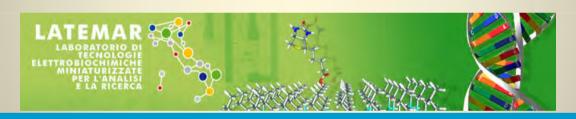
# Thermal FEM Simulation of a Multilevel Lab on Chip Device for Genetic Analysis

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### **Outline**

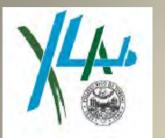
Introduction

 $\chi_{Lab}$  – Materials and Microsystems Laboratory

Loc devices

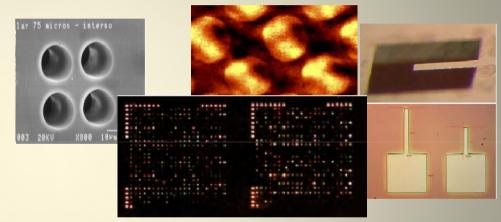
- Loc Design and Fabrication
- Experimental Set-up
- Genetic Protocol Thermal Needs
- Comsol FEM Model Details
- FE Model Validation: Experimental Measurement vs Fem Results
- FEM Results
- Conclusion and Future Work

# **Introduction** - $\chi_{lab}$ Materials and Microsystems Laboratory

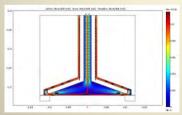


Materials and Microsystems Laboratory, is managed by Politecnico di Torino and works on the design and realization of micro and nano systems prototypes with a specific focus on technological transfer.

http://www.polito.it/micronanotech











MEMS simulation activity is transversal to most of  $\chi_{Lab}$  research projects and required for the design of microstructures or for their performance prevision. F.E.M. Simulations of microstructures behaviour is carried out by Comsol<sup>TM</sup> thanks to its great multiphysics capabilities and Coventorware<sup>TM</sup>.

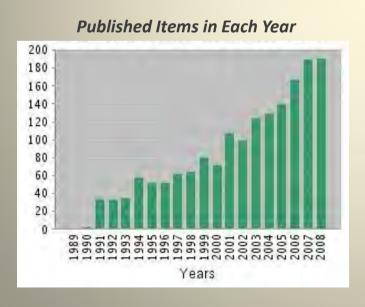
### Introduction – LOC Devices

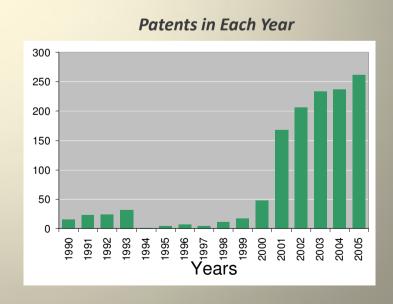
#### What is a Lab On a Chip?

• It is a device that integrates one or several laboratory functions into a miniaturized platform.

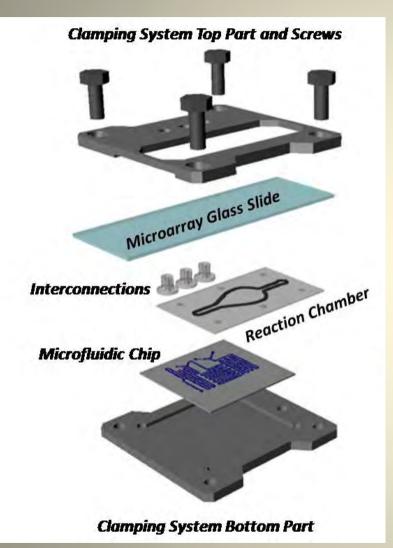
#### **International Interest on LOC**

• A big boost in research and commercial interest came in the mid 1990's, when it turned out to provide interesting tools for genomics applications, like capillary electrophoresis and DNA microarrays.

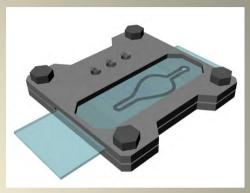




# LOC Design and Fabrication



**Exploded view of the multilevel LOC platform** 

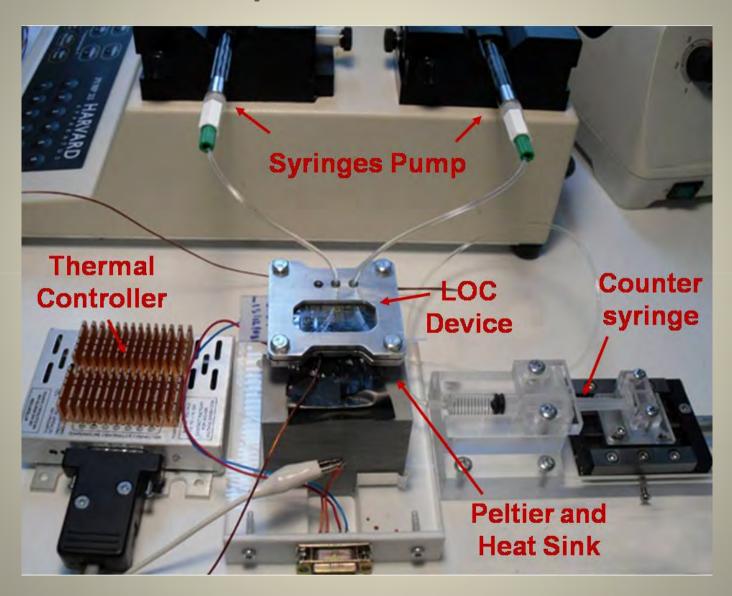


Assembly of the LOC platform

#### LOC features:

- Multilevel platform;
- Multi inlets microfluidics with passive mixers;
- Microstructured reaction chamber with O-ring like retention system;
- Microarray reversibly interfaced with reaction chamber;
- Clamping system;
- Ad hoc interconnections for inlets and outlets tubes;

# **Experimental Set-up**



### **Genetic Protocol Thermal Needs**

...for example

I) Initial Condition at RT

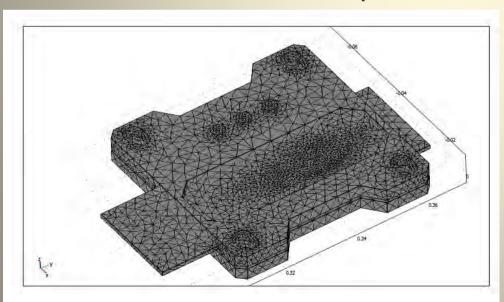
II) DNA Denaturation at 95° C

III) Hybridization Performed at 60° C.

#### Into reaction chamber

### **A proper Thermal FEM Model**

can be used in order to estimate the Temperature Values

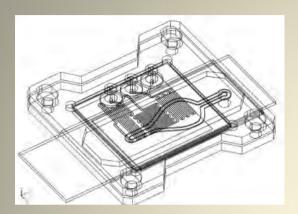




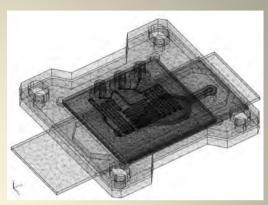
It is difficult to measure experimentally this temperature value being the reaction chamber inaccessible



## **Comsol FEM Model Details**



<u>CAD Model</u>: the import CAD module permits to import the 3D geometry of the whole device directly into the pre-processor of Comsol



#### **FEM Model:**

- *Number of DOF = 29808*
- Number of Tetrahedral Elements = 85939
- Elements Type = Lagrange Linear
- Time Dependent Analysis
- Solver = Linear System Solver (Direct UMFPACK)

Material Properties						
Model Part	Clamping System	Glass Slide	Interconnections and Reaction Chamber	Chip (top layer)	Chip (bottom layer)	Reagents Volume
Material	Aluminum	Corning 7740 (Pyrex)	PDMS	Corning 7740 (Pyrex)	Silicon	Water
Thermal Conductivity k [W/(m*K)]	160	k(T)	k(T)	k(T)	163	k(T)
Density ρ [kg/m³]	2700	ρ(Τ)	ρ(Τ)	ρ(Τ)	2330	ρ(Τ)
Heat Capacity at constant pressure C <sub>p</sub> [J/(kg*K)]	900	C <sub>p</sub> (T)	C <sub>p</sub> (T)	C <sub>p</sub> (T)	703	C <sub>p</sub> (T)

# **Comsol FEM Model Details – Internal Boundary Conditions**

The LOC was composed of different parts and materials. Comsol <u>ASSEMBLY MODE</u> was used in order to activate some settings for those <u>internal boundaries</u> that are particularly important for the heat transfer through different layers

$$-\mathbf{n}_{down} \cdot (-k\nabla T)_{down} = \frac{k_{res}}{d_{res}} (T_{up} - T_{down})$$

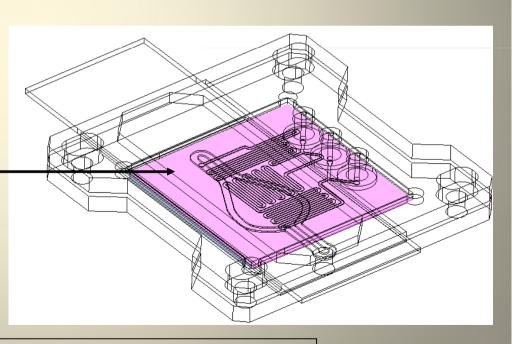
$$-\mathbf{n}_{up} \cdot (-k\nabla T)_{up} = \frac{k_{res}}{d_{res}} (T_{down} - T_{up})$$

#### thin thermally resistive layer

contact surface between the chip and the bottom part of the clamping

 $k_{res}$  is the thermal conductivity [W/(m·K)]

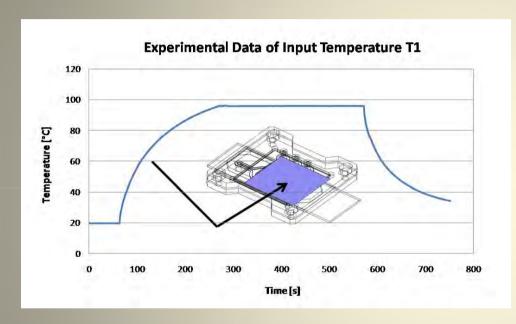
d<sub>res</sub> the thickness (m) of the **thin thermally resistive layer** 



 $k_{res}$  and  $d_{res}$  are referred to the thermal grease

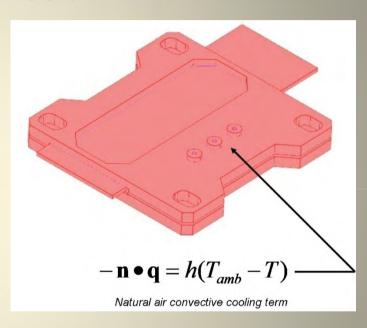
# **Comsol FEM Model Details - External Boundary Conditions**

ullet Dirichlet Condition that prescribes a specified temperature on a boundary  $\Omega$  [eq. 1]



$$T = T1(t)$$
 on  $\partial\Omega$  [eq.1]

• Neumann Condition that specifies the heat flux [eq. 2]



$$-\mathbf{n} \bullet \mathbf{q} = h(T_{amb} - T)$$
 on  $\partial \Omega$  [eq.2]

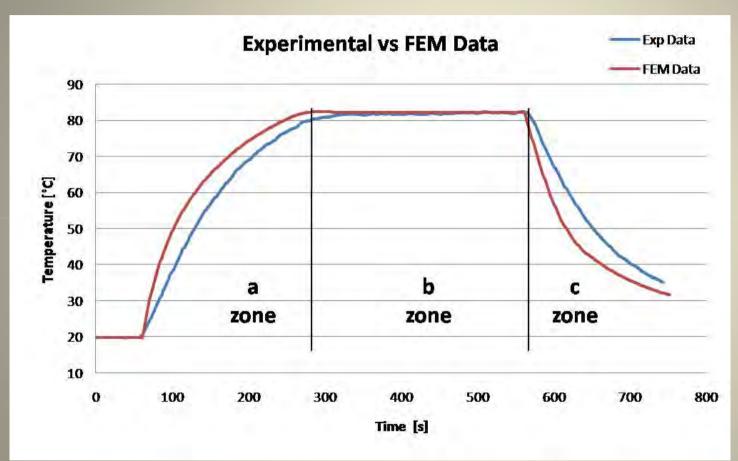
 $q = -k\nabla T$  is the conductive flux vector [W/m<sup>2</sup>]

**n** is the normal vector of the boundary, pointing out from the domain

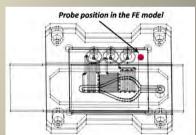
h is a heat transfer coefficient [(W/(m²·K)]

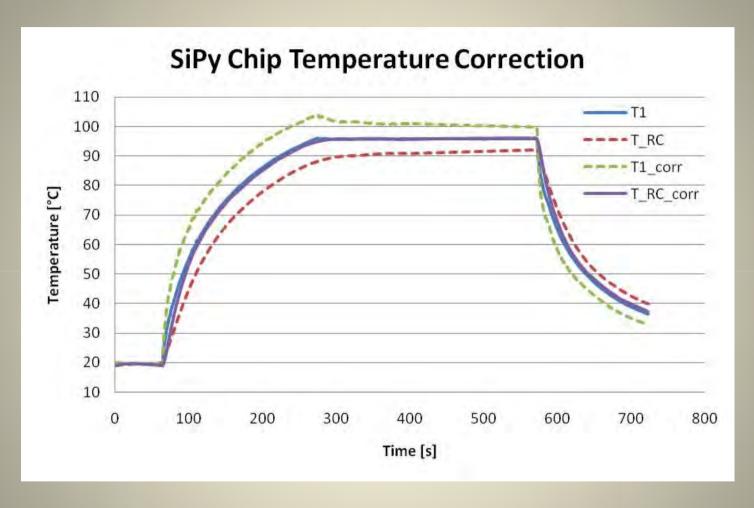
 $T_{amb}$  is the room temperature

# FE Model Validation: Experimental Measurement vs Fem Results

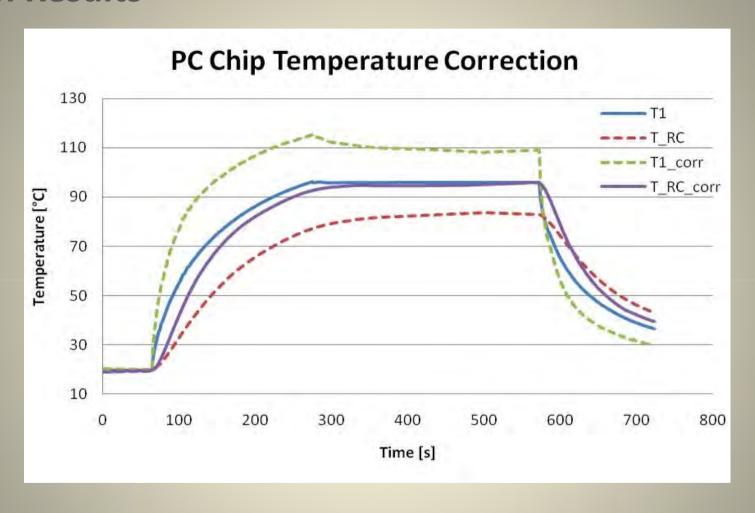




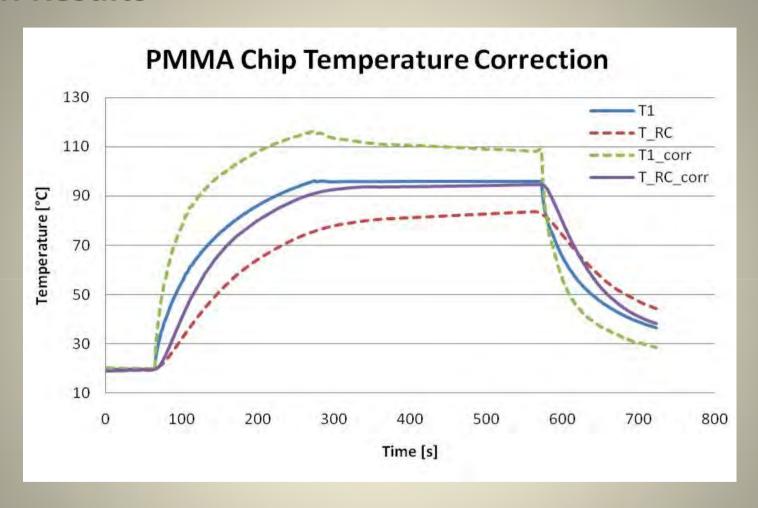




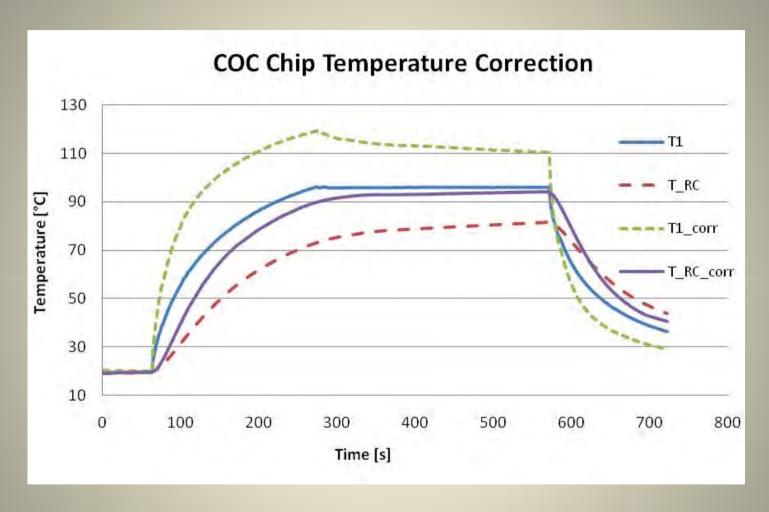
- T1 = Temperature input curve
- T\_RC = Temperature into the RC before the correction
- $T1\_corr = T1+\Delta T$  ( $\Delta T$  is the correction factor)
- T\_RC\_corr = Temperature into the RC after the correction



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### **Conclusion and Future Work**

#### Conclusion

- In this work, a FE model to monitor the temperature values into the reaction chamber of a LOC device is illustrated
- Among all the polymers analyzed, the PolyCarbonate (PC) performs better, from a thermal point of view
- This FE model allows to correct the temperature profile to be applied to the bottom part of the clamping system, to obtain the temperature profile into the reaction chamber according with the genetic protocols that have to be implemented in (DNA denaturation temperature in this case)

#### **Future** work

- Implement the FE model on the Comsol 4.0a to perform parametric time dependent analyses. In this way it will be possible to determine, through a "one-step" calculation, the minimum thickness of the chip that both maximizes the heat transfer and also allows to obtain the required temperature into the reaction chamber
- Add the Structural Mechanics module to explore the mechanical stress and strain of the whole device. In this way it will be possible to further optimize the geometry of the device in the region of the contact area between the reaction chamber and the microarray glass slide, where a reversible sealing is necessary

Thanks for your

# Attention